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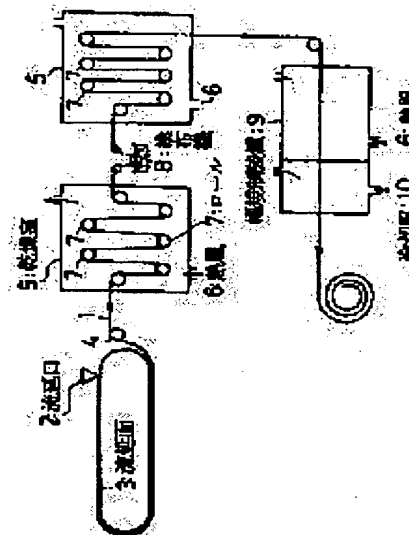
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(54) MANUFACTURE OF SUBSTRATE FOR PHOTOGRAPHIC SENSITIZED MATERIAL

(57)Abstract:

PURPOSE: To manufacture a film whose plane properties are not spoiled even if high-speed film making by high-temperature frying is performed, by a method wherein the film is stretched in a widthwise direction at the specific rate in a final process of the drying where a remaining solvent becomes a predetermined ratio or less.

CONSTITUTION: A cellulose triacetate dope is cast onto a casting surface 3 through a casting part 2, a film 1 formed by the same is peeled off by a peeling part 4 and the film 1 is dried by hot air 6 during running between rolls 7 within a drying chamber 5. Primer coating for photographic sensitized material is performed and dried in the drying chamber further. At a point of time when the residual solvent is about 10% or less, the film is led to a width regulating device 9, stretched by 2-6% in a widthwise direction, after the film is cooled further as it is under a tensed state and wound up. Thus, high-temperature and high-speed drying become possible, and a film making speed can be improved drastically, and after a photographic emulsion is applied to a substrate of the cellulose triacetate film, even at the time of processing into a photographic film product, no problem by processing scraps is generated.



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